

	Hits	Search Text	DBs
41	38	(((resist or photoresist or photosensitive or (radiation near5 sensitive)) near16 (mask or pattern\$4 or opening) near24 (strip\$4 or etch\$4 or (dry near5 etch\$4) or RIE or ash\$4 or mill\$4 or (ion near9 beam near4 etch\$4) or plasma)) same (shrink\$4 or reduc\$4 or remov\$4 or etch\$4 or strip\$4) same (sidewall or surface or profile or via or trench or pattern or mask or residu\$3 or side\$3surface or top\$4surface) same (((sulfur near2 oxide) or (sul\$3ur near2 \$2oxide) or ("SO.sub.2") or (sul\$2ur near9 containing)) near28 (Ne or Ar or Xe or Kr or "N.sub.2" or nitrogen or neon or argon or xenon or krypton or "CO" or "CO.sub.2" or (carbon near9 dioxide) or (carbon near9 \$4oxide)))) and ((substrate or wafer or platen or device) same (antireflect\$4 or (organic near9 antireflect\$4) or (organic near9 ARC) or ARC or BARC))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
42	76	(((resist or photoresist or photosensitive or (radiation near5 sensitive)) near16 (mask or pattern\$4 or opening) near24 (strip\$4 or etch\$4 or (dry near5 etch\$4) or RIE or ash\$4 or mill\$4 or (ion near9 beam near4 etch\$4) or plasma)) same (shrink\$4 or reduc\$4 or remov\$4 or etch\$4 or strip\$4) same (sidewall or surface or profile or pattern or mask or residu\$3) same (((sulfur near2 oxide) or (sul\$3ur near2 \$2oxide) or ("SO.sub.2") or (sul\$2ur near9 containing)) near28 (Ne or Ar or Xe or Kr or "N.sub.2" or nitrogen or neon or argon or xenon or krypton or "CO" or "CO.sub.2" or (carbon near9 dioxide) or (carbon near9 \$4oxide))))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
43	36	(((resist or photoresist or photosensitive or (radiation near5 sensitive)) near16 (mask or pattern\$4 or opening) near24 (strip\$4 or etch\$4 or (dry near5 etch\$4) or RIE or ash\$4 or mill\$4 or (ion near9 beam near4 etch\$4) or plasma)) same (shrink\$4 or reduc\$4 or remov\$4 or etch\$4 or strip\$4) same (sidewall or surface or profile or pattern or mask or residu\$3) same (((sulfur near2 oxide) or (sul\$3ur near2 \$2oxide) or ("SO.sub.2") or (sul\$2ur near9 containing)) near28 (Ne or Ar or Xe or Kr or "N.sub.2" or nitrogen or neon or argon or xenon or krypton or "CO" or "CO.sub.2" or (carbon near9 dioxide) or (carbon near9 \$4oxide)))) and (BARC or (bottom near5 ARC) or antireflect\$4 or (bottom near4 antireflect\$4 near6 layer))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB